Applications of Raman Spectroscopy in Material Science: Material Characterization and Temperature Measurements

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Raman spectroscopy is a powerful tool for characterizing materials and measuring temperatures. Synthesis of MoS2 films, a novel material with applications in semiconductor technology, requires accurate and robust characterization. We applied Raman spectroscopy to characterize CVD synthesized MoS2. This technique will provide information about existence and quality of these materials. In addition, we used Raman spectroscopy to measure and calibrate temperature in mechanical testing devices. These devices consist of a circuit designed for Joel heating of the samples and allow for mechanical measurements to be taken at elevated temperatures. Our aim is to correlate the input voltage or current to the temperatures reached in the samples.

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Methods (cont.)



Introduction

Raman Spectroscopy:

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A powerful tool to characterize chemical and physical properties of materials. Here I Have Applied This Technique to:

Molybdenum Disulfide (MoS₂)

Goal: Synthesis of single- and few-layered MoS₂ by Chemical Vapor Deposition (CVD) method.

---> Chemical and quality characterization of MoS₂

Mechanical Testing Device

Goal: Mechanical testing at elevated temperatures

--->To correlate the input power to ohmic heating of the device by means of Raman shift analysis





Fig. 1 3D representation of the structure of MoS₂^[1]

Fig. 2 Mechanical Testing Device [2]

Methods

CVD Method





Fig. 7 A simplified schematic of an experiment

1. Pass current through the device for Ohmic Heating 2. Scan the device via Raman Microscope after 90 sec. of heating and record the spectra 3. Turn off the power supply and wait for 2 min. (for the device to cool down) 4. Acquire similar data for different voltages 5. Quantify silicon band position for each voltage and

Experimental Procedures



The equation (3) is used to find the relationship between Raman shift and the corresponding temperature and input electrical current



Results and Discussion (cont.)

Single-layered or Few layered MoS₂





Fig. 10 SEM images of MoS₂ films (shown by red arrows) and gold particles on silicon substra





Fig. 11 MoS₂ films synthesized by CVD method on gold substrate

MoS₂ is on the whole surface. The red arrow shows the suspended MoS₂. ---> Easy to remove it from Au



References

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